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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/564,582	01/12/2006	Celine Juliette Detecheverry	NL03 0878 US	3317
24738	7590	03/19/2007	EXAMINER	
PHILIPS ELECTRONICS NORTH AMERICA CORPORATION			BAISA, JOSELITO SASIS	
INTELLECTUAL PROPERTY & STANDARDS			ART UNIT	PAPER NUMBER
1109 MCKAY DRIVE, M/S-41SJ			2832	
SAN JOSE, CA 95131				
SHORTENED STATUTORY PERIOD OF RESPONSE	MAIL DATE		DELIVERY MODE	
3 MONTHS	03/19/2007		PAPER	

Please find below and/or attached an Office communication concerning this application or proceeding.

If NO period for reply is specified above, the maximum statutory period will apply and will expire 6 MONTHS from the mailing date of this communication.

Office Action Summary	Application No.	Applicant(s)
	10/564,582	DETECHEVERRY ET AL.
	Examiner Joselito Baisa	Art Unit 2832

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --
Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) Responsive to communication(s) filed on ____.
- 2a) This action is FINAL. 2b) This action is non-final.
- 3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) Claim(s) 1-22 is/are pending in the application.
 - 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
- 5) Claim(s) _____ is/are allowed.
- 6) Claim(s) 1-22 is/are rejected.
- 7) Claim(s) _____ is/are objected to.
- 8) Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) The specification is objected to by the Examiner.
- 10) The drawing(s) filed on 1/12/2006 is/are: a) accepted or b) objected to by the Examiner.
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
 - a) All b) Some * c) None of:
 1. Certified copies of the priority documents have been received.
 2. Certified copies of the priority documents have been received in Application No. _____.
 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

1) <input checked="" type="checkbox"/> Notice of References Cited (PTO-892)	4) <input type="checkbox"/> Interview Summary (PTO-413)
2) <input type="checkbox"/> Notice of Draftsperson's Patent Drawing Review (PTO-948)	Paper No(s)/Mail Date. _____
3) <input checked="" type="checkbox"/> Information Disclosure Statement(s) (PTO/SB/08)	5) <input type="checkbox"/> Notice of Informal Patent Application
Paper No(s)/Mail Date <u>1/12/2006</u> .	6) <input type="checkbox"/> Other: _____

DETAILED ACTION

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1-22 are rejected under 35 U.S.C. 102(b) as being anticipated by Hiromoto

[JP2001230375A].

Hiromoto discloses a substrate having a first major surface 1,
an inductive element 14b fabricated on the first major surface of the substrate, the inductive
element 14b comprising at least one conductive line,
a plurality of tilling structures 8b, 5b in at least one layer, wherein the plurality of tilling
structures 8b, 5b are electrically connected together and arranged in a geometrical pattern so as to
substantially inhibit an inducement of an image current in the tilling structures by a current in the
inductive element [Abstract, Figure 1a and 3].

With respect to claim 22, the claim is a method counterpart of structure of claim 1 and method
steps therefore are inherent for manufacturing a semiconductor device that has tilling structure.

Regarding claim 2, Hiromoto discloses the tilling structures 8b, 5b being made from tilling
structure material, wherein the plurality of tilling structures 8b, 5b are arranged in a pattern so that the
amount of tilling structure material in an area closer to the inductive element is smaller than the amount of
tiling structure material in an area farther away from the inductive element [Abstract, see Figure 3].

Regarding claim 3, Hiromoto discloses the tilling structures 8b, 5b are located at different layers, tilling structures at each layer being arranged in a geometrical pattern so as to substantially inhibit an inducement of an image current in the tilling structures 8b, 5b by a current in the inductive element 14b [Abstract, Figure 3].

Regarding claim 4, Hiromoto discloses the geometrical pattern of tilling structures 8b, 5b at two different layers is different in shape and/or orientation [Abstract, Figure 3].

Regarding claim 5, Hiromoto discloses the tilling structures 8b, 5b at different layers are electrically connected to each other [Abstract, Figure 3].

Regarding claim 6, Hiromoto discloses the tilling structures 8b, 5b are connected to a DC potential [Abstract, Figure 3].

Regarding claim 7, Hiromoto discloses the tilling structures 8b, 5b are a plurality of slender elongate elements [Abstract, Figure 3].

Regarding claim 8, Hiromoto discloses in the tilling structures are a plurality of substantially triangular elements 6 [Abstract, Figure 2c]

Regarding claim 9, the tilling structures 8b, 5b are locally oriented perpendicular to the at least one conductive line of the inductive element [Abstract, Figure 1b].

Regarding claim 10, Hiromoto discloses the elements 6 of the tilling structures 8b, 5b are locally oriented perpendicular to the at least one conductive line of the inductive element [Abstract, Figure 2c].

Regarding claim 11, Hiromoto discloses a ground shield 2 for shielding the inductive element 14b from a further layer [Abstract, Figure 1b].

Regarding claim 12, Hiromoto discloses the further layer is the substrate 1 [Abstract, Figure 1b].

Regarding claim 13, connection means electrically connecting the plurality of tilling structures 8b, 5b with the ground shield 2 without creating a conductive loop [Abstract, Figure 1b].

Regarding claim 14, Hiromoto discloses the tilling structures 8b, 5b are formed in a region other than a region directly below the inductive element 14b [Abstract, Figure 1b].

Regarding claim 15, Hiromoto discloses a passive element [Abstract, Figure 3].

Regarding claim 16, Hiromoto discloses the further passive element is a capacitive element [Abstract, Figure 3].

Regarding claim 17, the capacitive element comprises two capacitor electrodes 8b, 2 at least one of the capacitor electrodes being formed by a plurality of tilling structures [Abstract, Figure 3].

Regarding claim 18, Hiromoto discloses a capacitor electrode formed by a plurality of tilling structures 8b, 5b leads to a metal or polysilicon 5b region density in the inductor vicinity respecting the design rules of advanced IC technologies [Abstract, Figure 1b].

Regarding claim 19, Hiromoto discloses one capacitor electrode of the capacitive element is formed by the ground shield 2 [Abstract, Figure 1b].

Regarding claim 20, Hiromoto discloses the integration of the capacitive element with the inductive element 14b is optimized to respect the metal pattern density in advanced silicon technologies [Abstract, Figure 1b].

Regarding claim 21, Hiromoto discloses the distance between the capacitive element and the inductive element 14b is large enough to avoid a dominant fringe coupling between them [Abstract, Figure 1b].

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Joselito Baisa whose telephone number is (571) 272-7132. The examiner can normally be reached on M-F 5:30 am to 2:00 pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Elvin Enad can be reached on (571) 272-1990. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Art Unit: 2832

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Joselito Baisa
Examiner
Art Unit 2832

jsb



ELVIN ENAD
SUPERVISORY PATENT EXAMINER
15 March 17